

IN THE CLAIMS:

Please amend the claims as follows.

1. (Currently Amended) A resist stripping equipment, comprising:
a stripping solution tank in which resist stripping solution is preserved;
a resist stripping chamber in which a substrate covered with resist is accommodated and resist stripping solution is supplied onto the substrate;
a spray which is connected to the stripping solution tank and sprays the resist stripping solution into the resist in the resist stripping chamber;
a solution line which supplies the sprayed resist stripping solution from the resist stripping chamber to the resist stripping tank;
a gas line which supplies a mixed gas containing a resist stripping solution component from the resist stripping container to outside;
a gas/liquid separation block which is connected to the resist stripping chamber the gas line, and which separates the resist stripping solution component from the introduced mixed gas and to which the mixed gas containing a resist stripping solution component in the resist stripping chamber is introduced, and in which the resist stripping solution component of the mixed gas is separated; and
a recovered resist stripping solution line supply block which is connected to the gas/liquid separation block and supplies the separated resist stripping solution component to the stripping solution tank the resist stripping chamber.
2. (Original) The resist stripping equipment of claim 1, further comprising:
a separated gas supply unit which receives gas separated from the resist stripping solution component in the liquid/gas separation block and supplies the gas to the gas spout unit,
wherein the resist stripping chamber includes a gas spout unit.

3. (Original) The resist stripping equipment of claim 2, wherein the gas spout unit is disposed facing the substrate.
4. (Original) The resist stripping equipment of claim 1, further comprising:
an inert gas supply unit which is connected to the resist stripping chamber and supplies inert gas into the resist stripping chamber.
5. (Original) The resist stripping equipment of claim 4, comprising:
a plurality of the resist stripping chambers provided in multiple stages to communicate with each other;
a rinse chamber provided to communicate with one of the plurality of resist stripping chamber at a last stage, the rinse chamber being supplied with water;
the gas/liquid separation block connected to one of the plurality of resist stripping chamber at a first stage; and
the inert gas supply unit connected to the rinse chamber,
wherein the resist stripping solution is a water-based resist solution.
6. (Original) The resist stripping equipment of claim 4, comprising:
a plurality of the resist stripping chambers provided in multiple stages to communicate with each other;
a rinse chamber provided to communicate with one of the plurality of resist stripping chambers at a last stage, the rinse chamber being supplied with water;
the gas/liquid separation block connected to one of the plurality of resist stripping chambers at a first stage; and
the inert gas supply unit connected to one of the plurality of resist stripping chambers at the last stage,
wherein the resist stripping solution is a non-water-based stripping solution.